

## **ABSTRACT OF THE DISCLOSURE**

CMP pad dressers suitable for conditioning fixed abrasive CMP pads, as well as methods for the making and use thereof are disclosed and described. The CMP dressers are able to condition a fixed abrasive CMP pad without dislodging or substantially damaging any of the poles contained on the pad's polishing surface. In one aspect, the CMP pad dresser may include a substrate member having a working surface with a plurality of small projections. The projections may have a height less than that of the poles on the CMP pad, and in one aspect may have a height of less than 30 micrometers, and be spaced apart by a distance of less than about 150 micrometers. In another aspect, a carbonaceous layer may be formed on the working surface of the CMP pad dresser.